# Silicon Based Tracking at a Super B Factory Detector

Aaron Roodman Stanford Linear Accelerator Center Hawaii Super B Factory Workshop 2005

## Backgrounds

Predictions for SuperPEP beam configurations



from Markus Cristinziani

| Conf. | $I_{LER}$ | $I_{HER}$ | $\mathcal{L}(10^{33})$ |
|-------|-----------|-----------|------------------------|
| 0     | 2.2A      | 1.4A      | 8                      |
| 1     | 11A       | 4.8A      | 200                    |
| 2     | 15.5A     | 6.8A      | 700                    |
| 3     | 23A       | 10.1A     | 1000                   |

assumed an improvement factor of 20 in susceptibility to backgrounds compared to the BABAR drift chamber

Luminosity term completely dominates radiative Bhabha scattering BABAR simulations need to confirm effect can it be reduced? by what factor?

## **Occupancy** Limits

What is the occupancy limit in a Silicon Tracker? consider effects of occupancy on current BABAR SVT



all-Silicon tracking will be more sensitive to single hit efficiencies, given the small number of layers, so efficiency drop due to background occupancy is an important effect Occupancy Scaling BABAR DCH 1.7 - 2 cm diameter cells 260 cm long 2 µsec read-out

> Silicon Tracker 100 µm strips (50 µm pitch with floating strips) 25 cm long strips 400 nsec shaping time

Geometrical factor = 2000Time factor = 5Radiation Length factor = 0.015Total = 150

## Silicon Tracker

conceptual Silicon Tracker



5 layers Vertex Detector4 layers Tracking Detector

よりもためにはないたはなどのようでは、「「「」」







Aaron Roodman Stanford Linear Accelerator Center -



CST300 has 300µm Silicon sensors 100µm carbon fiber supports for inner 5 layers 300µm carbon fiber in outer 4 layers

## Mass Resolution



| Quantity                         | BABAR | SVT+DCH   | <b>CST300</b> | <b>CST200</b> | CST100    |
|----------------------------------|-------|-----------|---------------|---------------|-----------|
| $\Delta E(B^0 \to \pi^+\pi^-)$   | 22    | 23        | 35            | 30            | 25        |
| $\Delta E(B^0 \to \phi K_s^0)$   | 17    | 13        | 25            | 21            | 17        |
| $m(\phi \to K^+ K^-)$            |       | 2.5       | 2.9           | 2.7           | 2.5       |
| $m(K_S^0 \to \pi^+\pi^-)$        | 2.2   | 2.7       | 3.7           | 3.4           | 3.1       |
| $\Delta E(B^0 \to D^{*+}D^{*-})$ | 8.0   | 6.1       | 9.0           | 8.2           | 7.2       |
| $\Delta m (D^* - D^0)$           | 0.30  | 0.36(0.9) | 0.69(1.9)     | 0.67(2.0)     | 0.61(1.6) |
| $m(D^0 \to K^+ \pi^-)$           | 7.0   | 5.5       | 11.0          | 9.6           | 7.9       |

#### Mass Resolution



#### Design Considerations

#### Minimize material - no cooling in fiducial volume so no readout electronics either

#### Long ladders or long cables ?

| · · · · · · · · · · · · · · · ·              |             |            |  |  |  |  |  |
|--|-------------|------------|--|--|--|--|--|
| Min-i for 300µm Si is about 24,000 electrons |             |            |  |  |  |  |  |
| Shaping (µs)                                 | Length (cm) | Noise (e⁻) |  |  |  |  |  |
| 1  | 100         | 2200       |  |  |  |  |  |
| 1  | 200         | 3950       |  |  |  |  |  |
| 3  | 100         | 1250       |  |  |  |  |  |
| 3  | 200         | 2200       |  |  |  |  |  |

Agilent 0.5 µm CMOS process (qualified by GLAST)

from Bruce Schumm simultions at LCWS 05

occupancy increases in both space & time

Design with cables and very low mass support innovative support and cable plant needed

## More Design Considerations

Sensors integrate electronics (JFet, DepFet) allow thiner sensors

Double sided (tracking) or Single sided (momentor)

small Drift Chamber cells worse hit resolution affects high momentum tracks Silicon tracking poor low momentum resolution
Hybrid - Silicon & Gas chamber optimize momentum resolution, background susceptibility, track finding efficiency

## Conclusions

Luminosity background term Momentum Resolution Design of a low mass support New thin sensors Hybrid design